
Introducing Fast cooling solutions for RTP



DESCRIPTION

The AS-One 100, AS-One 150 and AS-Master RTP systems from Annealsys can now receive optional features to increase the cooling rate of the substrate at the end of the annealing cycle.

The cold wall chamber technology and the reactor design allow installation of additional equipment to increase the cooling rate of the substrate by a factor of 4 and up to 100°C/s down to room temperature.

Heating fast can easily be achieved using high amount of power but cooling fast is a much more complicated problem. Our engineers have developed innovative solutions to overcome this problem.

These new features open new routes for Rapid Thermal Processing development.

INFORMATION

Detailed technical information can be sent upon request at info@annealsys.com

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